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5/28/99  
P. J. em

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor: KAICHIRO NAKANO, et al.  
Serial No.: 09/036,219  
Filed: March 6, 1998  
Title: CHEMICALLY AMPLIFIED RESIST LARGE IN  
TRANSPARENCY AND SENSITIVITY TO EXPOSURE LIGHT  
LESS THAN 248 NANOMETER WAVELENGTH AND  
PROCESS OF FORMING MASK  
Examiner: J. CHU  
Group Art Unit: 1752

May 21, 1999

Box Non-Fee Amendment  
Assistant Commissioner for Patents  
Washington, D. C. 20231

RECEIVED

MAY 27 1999

AMENDMENT

GROUP 1700

S I R :

Responsive to the Office Action dated April 27, 1999, please amend the  
application as follows:

IN THE CLAIMS:

Please cancel claims 2, 4, 7 and 8 without prejudice.

REMARKS

In the outstanding Office Action restriction has been issued to elect the claims  
between claims 1-8, drawn to resist composition, classified in claim 430, subclass 270.1  
and claims 9-20, drawn to process of use, classified in class 430, subclass 325.

In addition an election requirement to elect a single species has been issued by the  
Examiner.

Any fee due with this paper, not fully  
covered by an enclosed check, may be  
charged on Deposit Acct. No. 08-1634

Filed by Express Mail  
(Receipt No. EM36676541B4S)  
on 5-21-99  
pursuant to 37 C.F.R.1.10.  
by Francis Doyle